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## Determination of thin silicon sample thicknesses using linear and nonlinear optical methods

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**Abstract content** (Max 300 words) **Formatting & Special chars**

Silicon (Si) continues to be a prominent material in microelectronics, optoelectronic, micromechanics, solar cells, and increasingly in photonics. Delicate Si devices can be shaped and/or modified by laser technology providing many kinds of controlled methods for e.g. doping, annealing, crystallization and ablation. Proper processing requires, however, a detailed understanding of the linear and nonlinear optical phenomena in Si. Some of the nonlinear phenomena may occur simultaneously and be difficult to discriminate like coherent two-photon absorption (TPA), free carrier absorption (FCA), and thermally induced absorption enhancement (TAE). In this work, a femtosecond (fs) Ti:sapphire laser tuned at 800 nm is applied to investigate the linear and nonlinear optical behaviours of thin Si samples in the 10  $\mu\text{m}$  to 30  $\mu\text{m}$  range by measuring the average laser power of the fs pulse train transmitted through the membranes as a function of the incident laser power. The experimental findings help to determine the thickness of the Si samples using a linear and FCA absorption methods, respectively.

**Apply to be considered for a student award (Yes / No)?**

Yes

**Level for award (Hons, MSc, PhD, N/A)?**

PhD

**Main supervisor (name and email) and his / her institution**

E. G. Rohwer (egr@sun.ac.za), Laser Research Institute, Stellenbosch University

**Would you like to submit a short paper for the Conference Proceedings (Yes / No)?**

Yes

**Please indicate whether this abstract may be published online (Yes / No)**

Yes

**Primary author:** Mr NDEBEKA, Wilfrid (Laser Research Institute, University of Stellenbosch)

**Co-authors:** Dr STEENKAMP, Christine (University of Stellenbosch); Prof. ROHWER, Erich (University of Stellenbosch); Prof. STAFAST, Herbert (Leibniz Institute of Photonic Technology, Albert-Einstein-Str. 9, 07745, Jena, Germany); Dr NEETHLING, Pieter (Laser Research Institute, University of Stellenbosch)

**Presenter:** Mr NDEBEKA, Wilfrid (Laser Research Institute, University of Stellenbosch)

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